REMARKS

Favorable reconsideration of this application in light of the following discussion is respectfully requested.

1-40 are presently active in this Claims Claims 13-40 have been withdrawn from consideration based on a Restriction Requirement issued on August 16, 2005. The present Amendment amends Claims 1, 5, and 7-8 without introducing any new matter or raising new issues.

In the outstanding Office Action, Claims 7-8 rejected under 35 U.S.C. § 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter that Applicants regard as rejected invention. Claims 1-2 and 4 were under 35 U.S.C. § 103(a) as unpatentable over Yoshida et al. (Japanese Patent Application No. 02-048259, Japanese Patent Publication No. 03-251395, hereinafter "Yoshida"), in view of Sota et al. (U.S. Patent No. 6,285,086, hereinafter "Sota"). Claims 3 were rejected under 35 U.S.C. § 103(a) as unpatentable over Yoshida in view of Sota, in further view of Otsuki et al. (U.S. Patent No. 5,633,529, hereinafter "Otsuki"). Claims 7-8 unpatentable under 35 U.S.C. § 103(a) as unpatentable over Yoshida in view of Sota, in further view of Dufresne et al. (U.S. Patent No. 6,537,459, hereinafter "Dufresne"). Claims 5-6 and 9-12 were indicated as allowable if rewritten to overcome the rejections under 35 U.S.C. § 112, second paragraph, and to be in independent form.

acknowledge with appreciation Applicants the indication of allowable subject matter. In response, Claim 5 is amended to recite all the features of independent Claim 1, thereby being in condition for allowance.

In response to the rejections of Claims 1-4 and under 35 U.S.C. § 103(a), Applicants respectfully

reconsideration of these rejections and traverse the rejections, as discussed next.

Briefly recapitulating, Applicants' Claim 1 relates to a method of making a reusable mold for forming a microelectronic The method includes, inter alia, the removing of material from portions of a base; and then depositing a mask material on at least some portions of said base.

applied reference, Yoshida Turning now to the describes a method of manufacturing a metal mold for drilling, wherein a metal plate 1 is etched to form recessed regions 6a (See Yoshida in the Abstract). Yoshida explains that a photoresist layer 2 is formed on an upper surface of the metal plate 1 (Yoshida, Figure 1a). Thereafter, selective light is used on the photoresist layer 2 to form a mask 4 onto the photoresist 2 by development processing (Yoshida, Figure 1b). The portions not covered by the mask 4 of the plate 1 and photoresist 2 are then removed by a selective etching (Yoshida, However, Applicants' Claim 1 requires that Figure 1c, 1d). first material from portions of a base are removed; and then a mask material is deposited on at least some portions of the In Yoshida, first a mask 4 is deposited, subsequently, material from the metal plate 1 is removed. Therefore, the applied reference Yoshida fails to suggest all the features of Applicants' independent Claim 1. In addition, the cited passages of the references Sota, Otsuki, and Dufresne are also silent on such a feature. Accordingly, Applicants respectfully traverse the rejections under 35 U.S.C. § 103(a) and request reconsideration thereof.

The present amendment is submitted in accordance with the provisions of 37 C.F.R. § 1.116, which after Final Rejection permits entry of amendments complying with requirements of form set forth in a previous final Office Action. As the present amendment merely amends Claims 1 and 7-8 to correct a formal

issue, and amends Claim 5 to be in independent form, it is respectfully requested that the present amendment be entered.

In view of the above, each of the presently pending claims in this application is believed to be in immediate condition for allowance. Accordingly, the Examiner is respectfully requested to withdraw the outstanding rejection of the claims and to pass this application to issue.

If, however, for any reason the Examiner does not believe that such action can be taken at this time, it is respectfully requested that he/she telephone applicants' representative at (908) 654-5000 in order to overcome any additional objections which he might have.

If there are any additional charges in connection with this requested amendment, the Examiner is authorized to charge Deposit Account No. 12-1095 therefor.

Dated: May 22, 2007

Respectfully submitted,

Nikolaus P. Schibli

Registration No.: 56,994.

LERNER, DAVID, LITTENBERG, KRUMHOLZ & MENTLIK, LLP

RROMHODZ & MENTELK, D

600 South Avenue West

Westfield, New Jersey 07090

(908) 654-5000

Attorney for Applicant

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